

|    | <b>Hit<br/>s</b> | <b>Search Text</b>                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                                      | <b>DBs</b>                                              |
|----|------------------|-------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|---------------------------------------------------------|
| 24 | 133              | ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal) same (resist or photoresist or photocur\$4) same (irradiat\$4 or illuminat\$4 or (UV near9 source) or excimer or KrF or ArF or e\$3beam or (electron near4 beam) or EUV or DUV or VUV)) and pattern\$3 and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask or (phase near5 shift\$4 near5 mask)) and ((\$4lithograph\$6 or photolithograph\$6) same (beam or laser or ion\$8assist\$5 or irradiat\$4 or (ion near9 beam)) same (nitrogen or hydrogen or Ar or Ne or Kr or He or alkane or hydrocarbon)) | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |
| 25 | 49               | ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal) same (resist or photoresist or photocur\$4) same (irradiat\$4 or illuminat\$4 or (UV near9 source) or excimer or KrF or ArF or e\$3beam or (electron near4 beam) or EUV or DUV or VUV or laser)) and pattern\$3 and (((pattern\$6 near5 device) or mask\$4 or reticle) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same (nitrogen or hydrogen or Ar or Ne or Kr or He or alkane or hydrocarbon))                                                                       | US-PGPUB;<br>USPAT;<br>EPO; JPO;<br>DERWENT;<br>IBM_TDB |